



[ThD1] Process & Mask

Session Date	November 13 (Thu.), 2025
Session Time	09:00-10:50
Session Room	Room D (Sydney Room, 2F)
Session Chair	Mr. Jeonghoon Lee (imec, Belgium)

[ThD1-1] [Plenary]

09:00-09:45

Advances in Lithography and Patterning for Logic and DRAM

Kurt Ronse (imec, Belgium)

[ThD1-2] [Invited]

09:45-10:15

EUV ECO Equal Maximizing Productivity

Heeyoul Lim (SK hynix Inc., Korea)

[ThD1-3] [Invited]

10:15-10:35

Recent Progress in Tin-Based Inorganic Molecular Resists for EUV Lithography and Proposal of Cyclic Siloxane Resist for Blue-X Lithography

Hyun-Dam Jeong (Chonnam Nat'l Univ., Korea)

[ThD1-4] [Invited]

10:35-10:50

Cartridge-Based Van Der Waals Printing for Versatile Device Integration

Dong Hyup Kim (Chonnam Nat'l Univ., Korea)